

Amendments to the Claims:

The following listing of claims will replace all prior versions, and listings, of claims in the application:

1. - 11. (Canceled)

12. (Currently Amended) A scanning exposure method comprising the steps of:

moving a mask having first and second patterns, and a substrate in synchronization; and

exposing the first and second patterns on the substrate,

wherein when the first and second patterns are exposed along a synchronous moving direction of the substrate, a part of the first pattern and a part of the second pattern overlap and are exposed, and a synchronous moving speed of the mask and the substrate when there is overlapping exposure is set different from a synchronous moving speed of the mask and the substrate when there is no overlapping exposure; and

wherein a position of a blind plate which sets an illumination region along a direction orthogonal to a scanning direction during a scanning exposure is changed during the scanning exposure so that an overlapping region in which the overlapping exposure is performed extends in a direction that differs from an arrangement direction of the patterns which are arranged parallel to the scanning direction.

13. (Previously Presented) The scanning exposure method according to claim 12, wherein the first pattern and a third pattern adjacent to the first pattern in a direction orthogonal to the synchronous moving direction on the substrate have pluralities of unit patterns arrayed in different predetermined directions, and when the first and third patterns are exposed, the patterns overlap each other in a direction different from the arraying direction of the unit patterns..

14. (Currently Amended) A scanning exposure method comprising the steps of:

moving a mask having a pattern, and a substrate with respect to a region illuminated with an exposing light, in synchronization; and
exposing the pattern on the substrate,
wherein a size of the illumination region in a direction intersecting with a synchronous moving direction of the substrate is synchronously changed during synchronous movement at the time of exposure in order that a locus of an end of the illumination region on the substrate is extended in a direction different from an arrangement direction of patterns which are arranged parallel to the synchronous moving direction.

15. (Original) The scanning exposure method according to claim 14, wherein the size of the illumination region is changed a plurality of times during the synchronous movement.

16. (Currently Amended) A scanning exposure system which moves a mask having a pattern, and a substrate, in synchronization, and exposes the pattern on the substrate, comprising:

an illumination region setting device which sets an illumination region of the mask; and

a changing device which synchronously changes a size of the illumination region in a direction intersecting with a synchronous moving direction of the substrate during synchronous movement at the time of exposure in order that a locus of an end of the illumination region on the substrate is extended in a direction different from an arrangement direction of patterns which are arranged parallel to the synchronous moving direction.

17. (Currently Amended) A scanning exposure system which moves a mask having a pattern, and a substrate, in synchronization, and exposes the pattern on the substrate, comprising:

an illumination region setting device which sets an illumination region of the mask; and

a changing device which changes a size of the illumination region in a direction different from a synchronous moving direction of the substrate during synchronous movement,

wherein the illumination region setting device includes a pair of blind plates which respectively have openings with a predetermined width in the synchronous moving direction and are movable in a direction that is different from the synchronous moving direction, and

wherein a position of an illumination region along a direction orthogonal to a scanning direction during a scanning exposure is changed during the scanning exposure so that an overlapping region in which an overlapping exposure is performed extends in a direction that differs from an arrangement direction of patterns which are arranged parallel to the scanning direction.

18. (Previously Presented) A scanning exposure system according to claim 17, wherein the illumination region has a pentagonal or hexagonal shape.

19. (Previously Presented) A scanning exposure system according to claim 17, wherein the illumination region setting device provides the illumination region which has triangular ends.

20. (Currently Amended) A scanning exposure system which moves a mask having a pattern, and a substrate, in synchronization, and exposes the pattern on the substrate, comprising:

an illumination region setting device which sets an illumination region of the mask; and

a changing device which changes a size of the illumination region in a direction different from a synchronous moving direction of the substrate during synchronous movement,

wherein ends of the illumination region are inclined relative to an arrangement direction of patterns which are arranged parallel to the synchronous moving direction, and are exposed to an illumination gradient.

21. (Currently Amended) A scanning exposure system which moves a mask having a pattern, and a substrate, in synchronization, and exposes the pattern on the substrate, comprising:

an illumination region setting device which sets an illumination region of the mask; and

a changing device which changes a size of the illumination region in a direction different from a synchronous moving direction of the substrate during synchronous movement and changes a position of the illumination region along a direction orthogonal to a scanning direction during a scanning exposure so that an overlapping region in which an overlapping exposure is performed extends in a direction that differs from an arrangement direction of the patterns which are arranged parallel to the scanning direction,

wherein the illumination region setting device includes at least one blind plate for providing the illumination region with a triangular end and at least one end light-shielding blind plate which covers the triangular end of the at least one illumination region.

22. (Previously Presented) A scanning exposure method according to claim 14, wherein the illumination region has a pentagonal or hexagonal shape.

23. (Previously Presented) A scanning exposure method according to claim 14, wherein the size of the illumination region in a direction intersecting with the synchronous moving direction of the substrate is continuously changed during the synchronous movement.

24. (Previously Presented) A scanning exposure method according to claim 14, wherein an adjacent pattern is exposed so as to be partially overlapped with the pattern of the mask which was formed on the substrate.

25. (Currently Amended) A scanning exposure method comprising the steps of:
moving a mask having a pattern, and a substrate, with respect to a region
illuminated with an exposing light, in synchronization; and
exposing the pattern on the substrate,
wherein a size of the illumination region in a direction intersecting with a
synchronous moving direction of the substrate is synchronously changed during synchronous
movement, a position of the illumination region along a direction orthogonal to a scanning
direction is changed during a scanning exposure so that an overlapping region in which an
overlapping exposure is performed extends in a direction that differs from an arrangement
direction of patterns which are arranged parallel to the scanning direction, and wherein an
overlapping part which is partially overlapped with the pattern is formed in a zigzag pattern.

26. (Currently Amended) A scanning exposure method according to claim 25,
wherein ~~the~~an adjacent pattern, which is adjacent to the pattern in an orthogonal direction to
the synchronous moving direction, is exposed so as to be partially overlapped with the pattern
of the mask which was formed on the substrate.

27. (Currently Amended) A scanning exposure method according to claim 25,
wherein ~~the~~an adjacent pattern which is adjacent to the pattern in the synchronous moving
direction is exposed so as to be partially overlapped with the pattern of the mask which was
formed on the substrate.

28. (Previously Presented) A scanning exposure method according to claim 26,
wherein the adjacent pattern which is adjacent to the pattern in the synchronous moving
direction is exposed so as to be partially overlapped with the pattern of the mask which was
formed on the substrate.

29. (Previously Presented) A scanning exposure system according to claim 20,
further comprising an alignment member which performs alignment between the mask and the

substrate to partially overlap a part of the pattern of the mask with a part of the pattern which was exposed on the substrate.

30. (Previously Presented) A scanning exposure system according to claim 29, wherein a synthesized pattern is formed by exposing a plurality of the patterns of the mask in a manner so as to partially overlap the plurality of the patterns.

31. (Currently Amended) A scanning exposure method comprising the steps of:
moving a mask having a pattern, and a substrate, with respect to an illumination region that is illuminated with an exposing light, in synchronization; and
exposing the pattern on the substrate,
wherein the illumination region is moved in a direction intersecting with a synchronous moving direction of the substrate during synchronous movement at the time of exposure so that an overlapping region in which an overlapping exposure is performed extends in a direction that differs from an arrangement direction of patterns which are arranged parallel to the synchronous moving direction.

32. (Previously Presented) A scanning exposure method according to claim 31, wherein a size of the illumination region in the direction intersecting with the synchronous moving direction of the substrate is continuously changed during the synchronous movement.